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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/635,982	08/07/2003	Same-Ting Chen	N1085-00130	1619
8933	7590 03/28/2005		EXAMINER	
DUANE MORRIS, LLP			MOHAMEDULLA, SALEHA R	
IP DEPARTN	- 		ART UNIT	PAPER NUMBER
PHILADELPHIA, PA 19103-7396			1756	
			DATE MAILED: 03/28/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)				
Office A - 41- to O memorate	10/635,982	CHEN, SAME-TIN	G			
Office Action Summary	Examiner	Art Unit				
	Saleha R. Mohamedulla	1756				
The MAILING DATE of this communication apperiod for Reply	The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply					
A SHORTENED STATUTORY PERIOD FOR REPI THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a re - If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statu Any reply received by the Office later than three months after the maili earned patent term adjustment. See 37 CFR 1.704(b).		nely filed s will be considered timely the mailing date of this co D (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 07.	August 2003.					
· · · · · · · · · · · · · · · · · · ·	is action is non-final.					
3) Since this application is in condition for allowed	ance except for formal matters, pro	secution as to the	merits is			
closed in accordance with the practice under	Ex parte Quayle, 1935 C.D. 11, 45	i3 O.G. 213.				
Disposition of Claims						
4) ☐ Claim(s) 1-7 is/are pending in the application. 4a) Of the above claim(s) is/are withdra 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-7 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/	awn from consideration.					
Application Papers	•					
9) The specification is objected to by the Examin 10) The drawing(s) filed on is/are: a) accomposed and applicant may not request that any objection to the Replacement drawing sheet(s) including the correct of the oath or declaration is objected to by the Examination.	cepted or b) objected to by the E e drawing(s) be held in abeyance. See ction is required if the drawing(s) is obj	e 37 CFR 1.85(a). ected to. See 37 CF	` '			
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Bureat * See the attached detailed Office action for a list	nts have been received. Its have been received in Application or the contraction of the c	on No d in this National \$	Stage			
Attachment(s)						
1) Notice of References Cited (PTO-892)	4) Interview Summary (
 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date 8/7/03. 	Paper No(s)/Mail Dai 5) Notice of Informal Pa 6) Other:		-152)			

Application/Control Number: 10/635,982 Page 2

Art Unit: 1756

DETAILED ACTION

Claims 1-7 are pending.

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 2. Claims 1-7 are rejected under 35 U.S.C. 102(b) as being anticipated by US# 5,965,301 to Nara et al.

Nara teaches gallium stain removal. A method for repairing a photomask by removing a residual defect in the photomask is provided which can solve problems, involved in repair of the photomask by the conventional laser beam irradiation, such as various types of maladjustments, limitation of focusing of a laser beam, creation of roughening in the repaired area, and problems, involved in repair of the photomask by focused ion beam irradiation, such as damage to a transparent substrate and a gallium stain. The method comprises the steps of: (a) applying actinic radiation to the residual defect area to remove the residual defect except for a defect edge region having a predetermined width from the periphery of the residual defect area over the whole periphery of the residual defect area; and (b) removing the defect edge region, remaining unremoved by the physical means, having a predetermined width from the periphery of the residual defect area over the whole periphery of the residual defect area by chemical etching with a chemical, the predetermined width being such that the influence of the actinic

radiation does not extend over the outside of the residual defect area and, at the same time, the etching time can be set so that the region having a predetermined width from the periphery is removed by the chemical etching without any substantial influence on other layers including a light-shielding layer (Abstract). Nara teaches a phase shift photomask (col. 4, lines 40-45). The claimed pH is inherent. Nara also teaches a focused ion beam and simultaneous etching (col. 3, lines 40-50 and 55-65). Nara also teaches gas etching (col. 4, line 60). The molecular weight of the polymer is also inherent.

Page 3

Conclusion

Any inquiry concerning this communication or earlier communications from the Examiner should be directed to Saleha Mohamedulla whose telephone number is (571) 272-1387. The Examiner can normally be reached Monday-Friday, from 8:00 AM to 4:30 PM. If attempts to reach the Examiner by telephone are unsuccessful, the Examiner's supervisor. Mark Huff, can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Saleha R. Mohamedulla

Patent Examiner

Technology Center 1700

March 21, 2005